

#3

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Hiromoto OHNO, et al.

Appln. No.: 09/822,211

Confirmation No.: 9864

Group Art Unit: Not Yet Assigned

Filed: April 2, 2001

Examiner: Not Yet Assigned

For: MEASURING METHOD FOR CONCENTRATION OF HALOGEN AND FLUORINE
COMPOUND, MEASURING EQUIPMENT THEREOF AND MANUFACTURING
METHOD OF HALOGEN COMPOUND

PRELIMINARY AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

Sir:

Prior to examination, please amend the above-identified application as follows:

IN THE SPECIFICATION:

Page 5, please delete the first full paragraph and replace it with the following new

paragraph:

A' On the other hand, perfluorocarbons such as tetrafluoromethane and hexafluoroethane are used as an etching gas or a cleaning gas in semiconductor device production processes.

Regarding the production process for such a fluorocarbon, various methods are known, for example, as shown below:

(1) reaction of ethane with F₂ in a jet reactor to form tetrafluoromethane (hereinafter occasionally referred to as "FC-14" or "CF₄"), or hexafluoroethane (hereinafter occasionally referred to as